WHAT IS CLAIMED IS:

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- 1. A multi-foil optic comprising:
- a plurality of flat plates each having a reflecting surface, and positioned normal to an arc to provide total external reflection to high energy radiation incident on the plates from a high energy radiation source, to focus the incident high energy radiation on a designated surface, wherein each plate has a thickness in the range of 50-70 μ m.
- 2. The multi-foil optic of claim 1, wherein the high energy radiation comprises X-ray radiation.
 - 3. The multi-foil optic of claim 1, wherein the high energy radiation comprises extreme ultraviolet (EUV) radiation.
 - 4. The multi-foil optic of claim 1, wherein the plates are made of glass.
- 15 5. The multi-foil optic of claim 1, wherein the plates are made of mica.
 - 6. A method for performing high energy radiation lithography, comprising the steps of:

receiving high energy radiation from a high energy radiation source;

focusing the high energy radiation from the high energy radiation source using a multi-foil optic;

receiving the focused high energy radiation from the multi-foil optic onto a lithographic specimen via a lithographic mask.

- 7. The method of claim 6, wherein the high energy radiation comprises X-ray radiation.
- 8. The method of claim 6, wherein the high energy radiation comprises extreme ultraviolet (EUV) radiation.

9. A high energy lithographic system, comprising:

a high energy source;

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a multi-foil optic for focusing high energy radiation from the high energy source; and

a mask, which receives focused high energy radiation from the multi-foil optic and selectively blocks some of the radiation to form a pattern on a specimen that is exposed to high energy radiation passing through said mask.

- 10. The high energy lithographic system of claim 9, wherein the high energy radiation comprises X-ray radiation.
- 15 11. The high energy lithographic system of claim 9, wherein the high energy radiation comprises extreme ultraviolet (EUV) radiation.